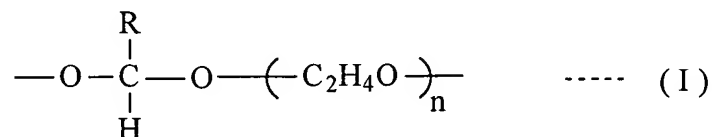


Claims:

1. A chemically amplified photosensitive resin composition comprising (A) an alkali-soluble novolak resin, (B) a resin or compound which in itself is insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid, (C) an acid generating agent and (D) a photosensitizing agent containing a quinonediazide group.

2. A chemically amplified photosensitive resin composition according to Claim 1, wherein said resin or compound which is itself insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid has a structural unit represented by the general formula (I):



wherein R represents a saturated alkyl group having 1 to 20 carbon atoms and n is an integer from 1 to 10.

3. A chemically amplified photosensitive resin composition according to Claim 1 or 2, which further comprises (E) an alkali-soluble acrylic resin.

4. A chemically amplified photosensitive resin composition according to Claim 3, wherein said alkali-soluble acrylic resin contains a structural unit derived from a (meth)acrylic acid, a structural unit derived from an alkylmethacrylate and, as required, a structural unit derived from styrene.

5. A chemically amplified photosensitive resin

composition according to Claim 3 or 4, wherein said alkali-soluble acrylic resin contains a structural unit derived from a hydroxyalkylmethacrylate, a structural unit derived from an alkylmethacrylate and, as required, a structural unit derived from styrene.

6. A chemically amplified photosensitive resin composition according to any one of Claims 1 to 5, which further comprises (F) a compound containing at least two vinyloxyalkylester groups.

7. A chemically amplified photosensitive resin composition according to any one of Claims 1 to 6, wherein the ratio by weight of said components (A) : (B) : (C) : (D) : (E) : (F) is 100 : 1 to 50 : 0.02 to 10 : 1 to 30 : 0 to 200 : 0 to 30.

8. A chemically amplified photosensitive resin composition according to any one of Claims 1 to 7, the composition being used in a layer thickness of 10 μm or more.